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*Mue*Tec installs Defect Review System "*Mue*Tec DefectCheck 5500" for Substrates up to 600 x 600 mm

_Mue_Tec has installed a Defect Review and Inspection System "_Mue_Tec DefectCheck 5500" with unrivalled optical resolution for large area substrates. DefectCheck is equipped with 248 nm illumination providing an optical resolution of sub 100 nm and uses transmitted light illumination as well as incident illumination. The system accommodates substrates up to 600 x 600 mm size besides a varity of smaller specimen.

The proceeding requirements on defect free products with structures of only some 100 nm size claim for enormous efforts regarding the final product inspection. To qualify obsolete defects as noncritical, critical or killer defects, it is neccesary to review them with best possible optical resolution using latest optical technology. For *Mue***Tec** equipment the used 248 nm illumination together with Vistec optics are state of the art since a few years.

*Mue***Tec** NanoStar software allows a timesaving review process due to its easy to use but very powerful NanoStar GUI. An automatically operating analysis, similar to the automatic ADC functions used in semiconductor manufacturing processes, is also provided by *Mue***Tec** NanoStar. This analysis tool helps to definitely classify questionable defects.

A special highlight of DefectCheck 5500 enables one to "Re-Scan" a suspicious defect with best possible optical resolution. "Re-Scan" is an attendant part of *Mue***Tec** NanoStar software.

The options of NanoStar give the user the possibility to track the performance of a single substrate or even a complete product batch between different manufacturing processes.